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Title: METHOD FOR CONTROLLING ACCURACY AND REPEATABILITY OF AN

ETCH PROCESS

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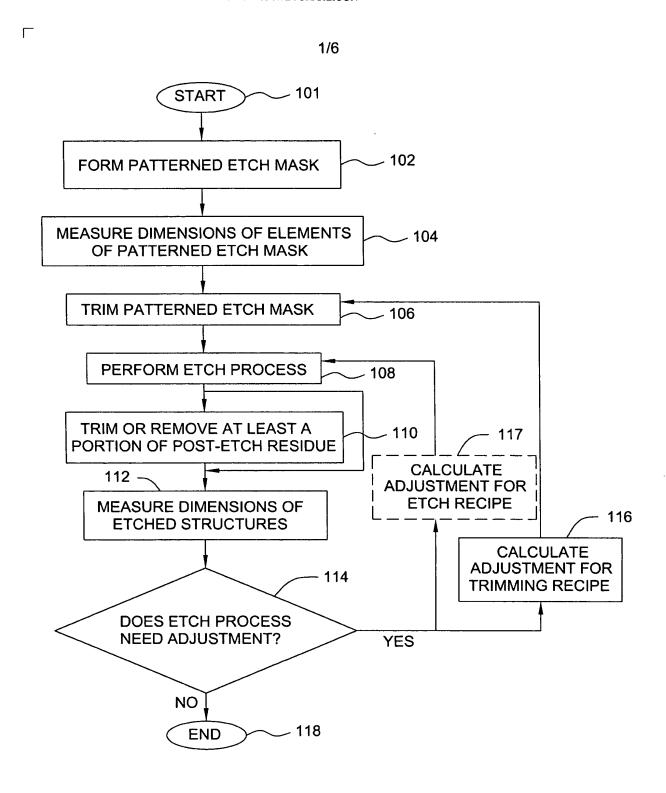


FIG. 1

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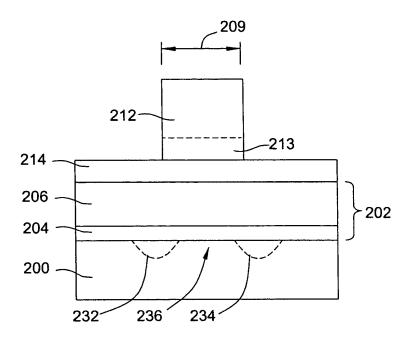


FIG. 2A

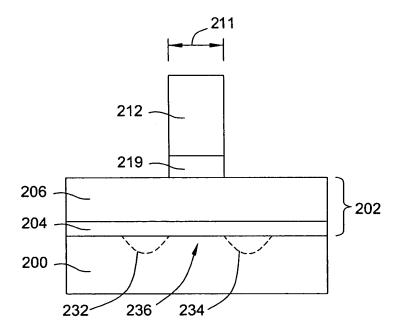


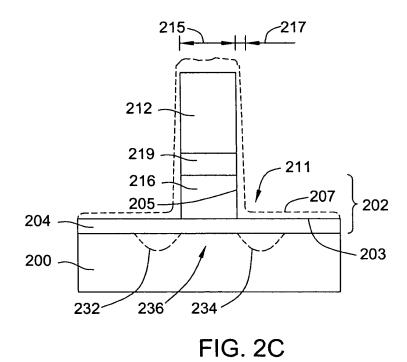
FIG. 2B

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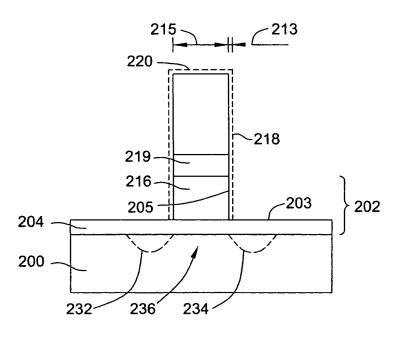


FIG. 2D

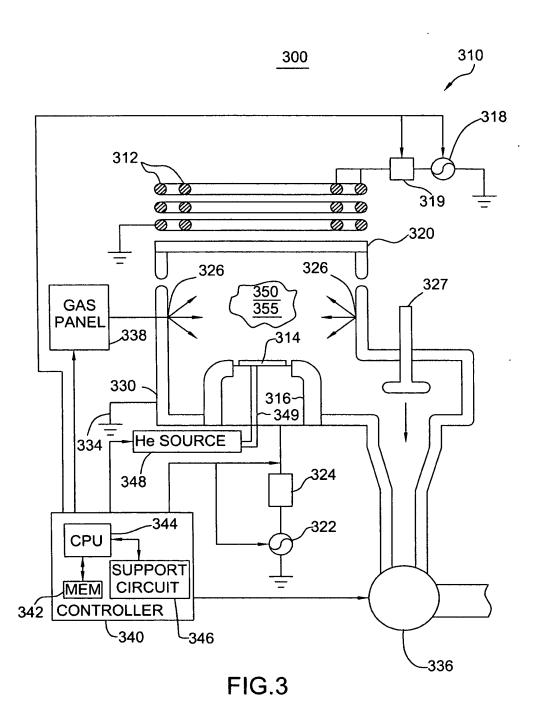
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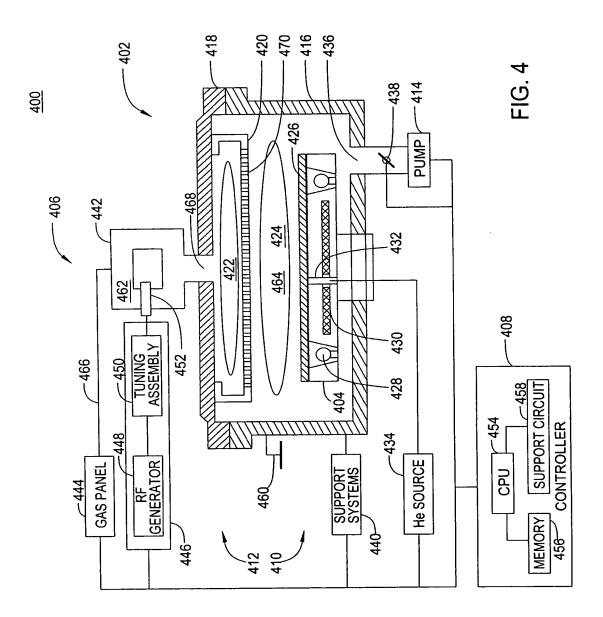
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